

# Online Semi-radius Probe Tip Cleaning and Reshaping

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# Agenda

- Acknowledgements
- Background info
- Setup and measurement technique
- Contact resistance results
- Cleaning recipe parameters to consider
- Silicone vs polymer based materials
- Summary
- Future work

# Acknowledgements

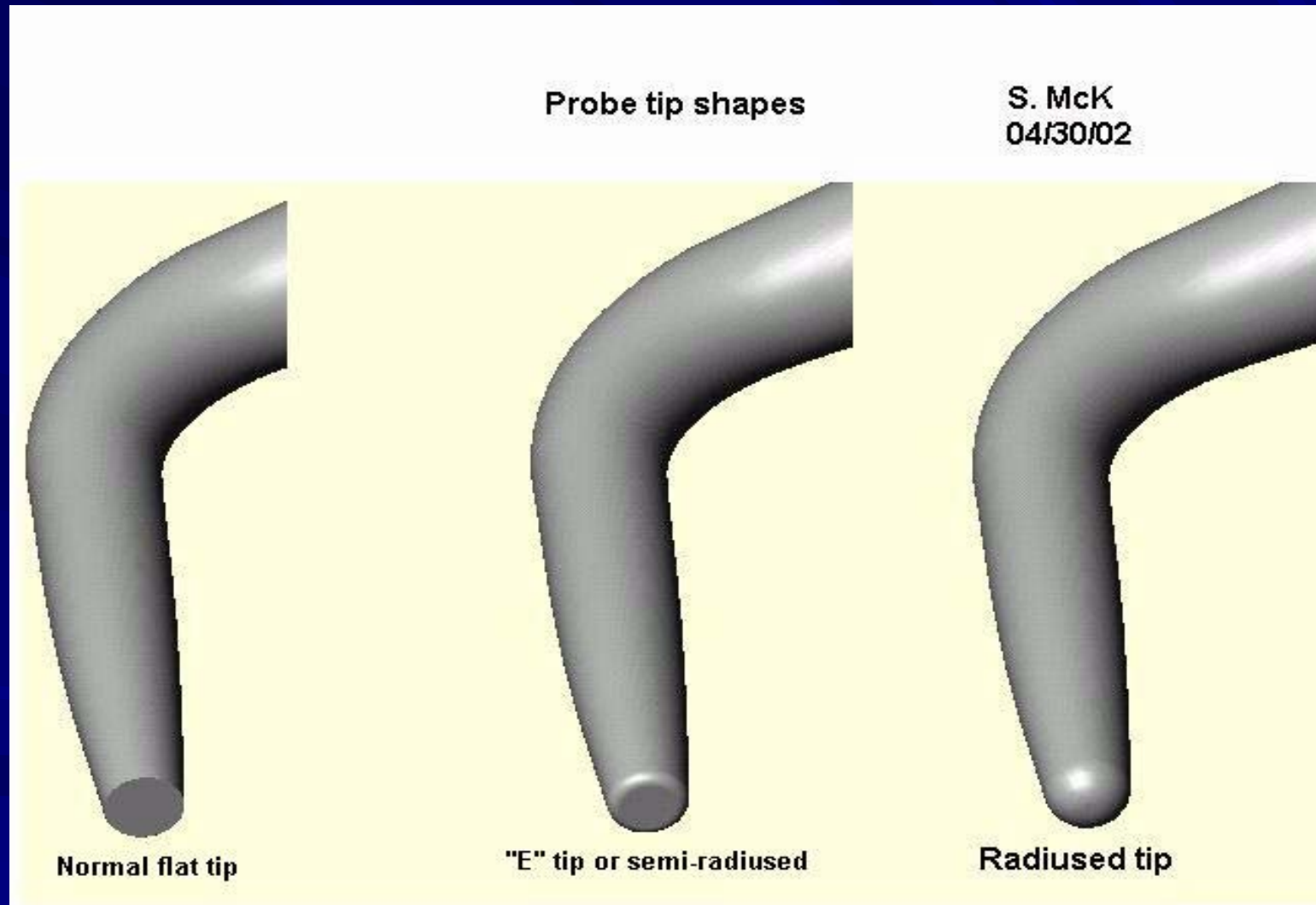


- Jack Courtney
- John Cartier
- Steve Duda
- Les Griffith
- Rob Holwager



Glen Langsman  
Josh Pendergast

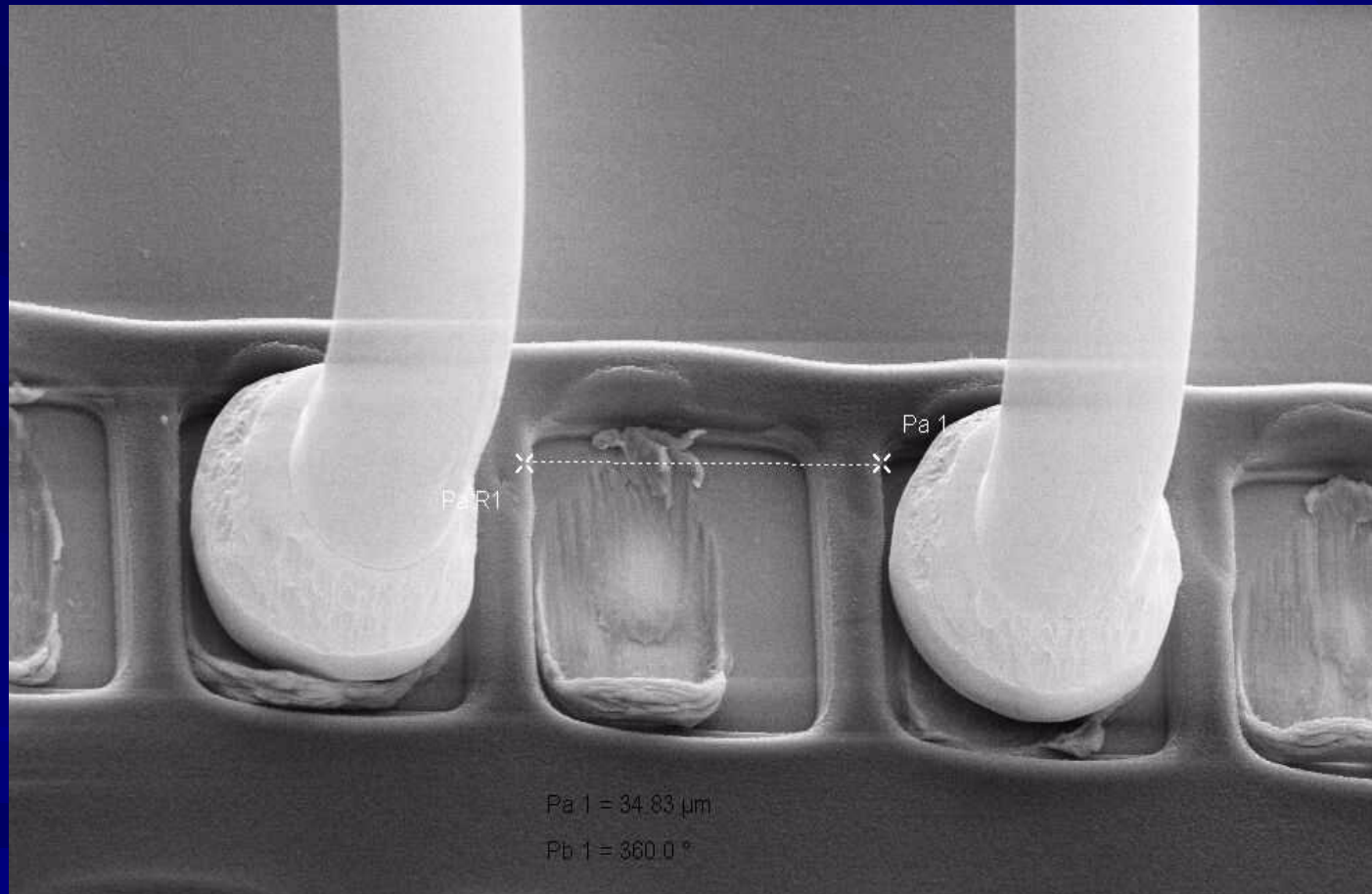
# Basic cantilever probe types



# Why Semi-radius?

- Lower pad damage in general for today's soft aluminum
- Approximately same scrub length as flat tip while reducing the amount of material removed from base material
- Equivalent contact resistance to flat or full radius tip
- Reflectivity similar to flat tip for prober and probe metrology alignment (easier to align to vs. full radius material)

# Bonding – Semi radius tips



Pad opening shown is 29X29 microns - running out of room!

# The problem with Semi-radiused probes

- Variable tip geometry using standard material cleaning solutions
- No insitu solution – non silicone based
- Either flat tip or radiused tip solution but no semi-radiused solution

# Traditional way to maintain semi-radius probe tips

- Use elastomeric abrasive i.e. polymer based material – continues to radius tips
- Remove periodically to reshape (put a flat back on it)



# The solution

- Two part cleaning – insitu
  - Abrasive material for flat tip – SiC
  - Elastomeric material for radius tip and removes stringers (contact pad and cleaning detritus)

# Two basic cleaning mediums

## ■ Two part cleaning – insitu

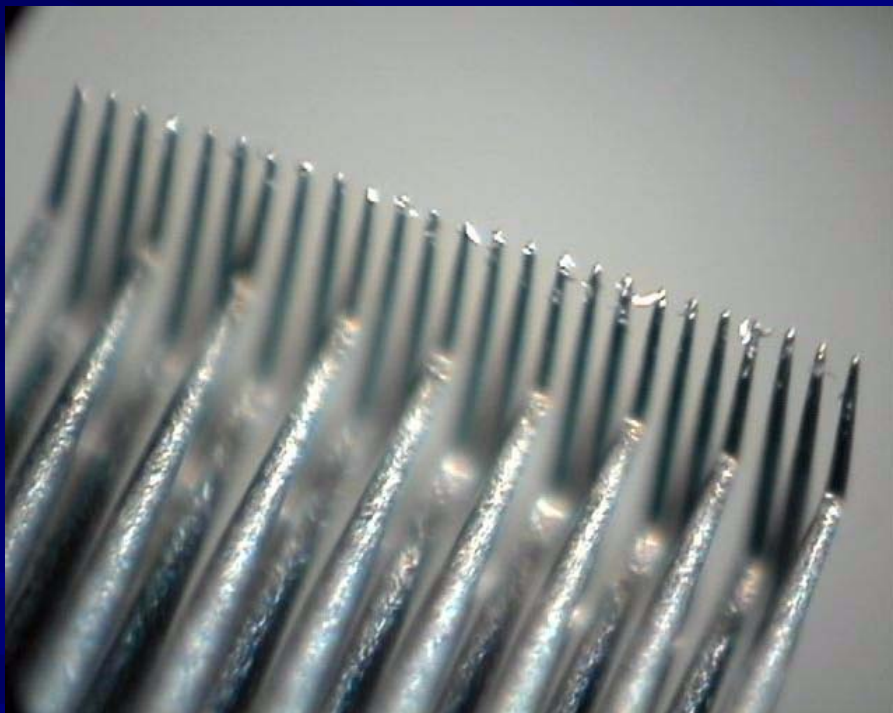
- Solid Abrasive material for flat tip – SiC (Silicon Carbide)
- Elastomeric material for radius tip and removes stringers (contact pad detritus)
- Order is important – see data

# Typical recipes

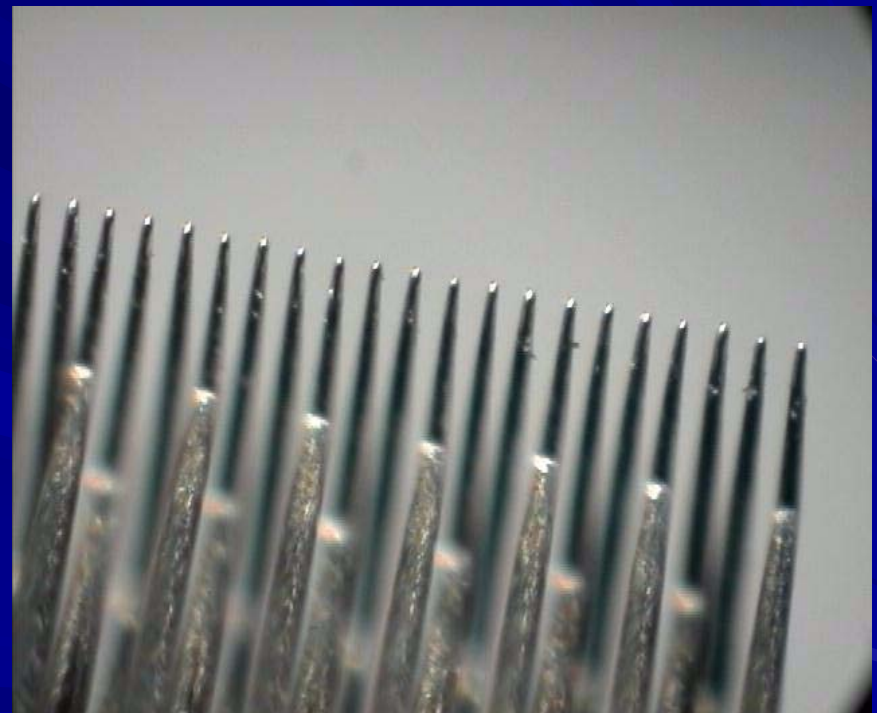
- 5 -10 up/down touchdowns on each medium
  - SiC abrasive removes all detritus down to base material (flat tip)
  - Elastomeric abrasive -removes probing/cleaning detritus (radius tip)
- Use same OD as with product for SiC, OD + 30% for elastomeric (typical) - pitch dependant
- Move to new location between Up/Down

# Polymer based abrasive clean

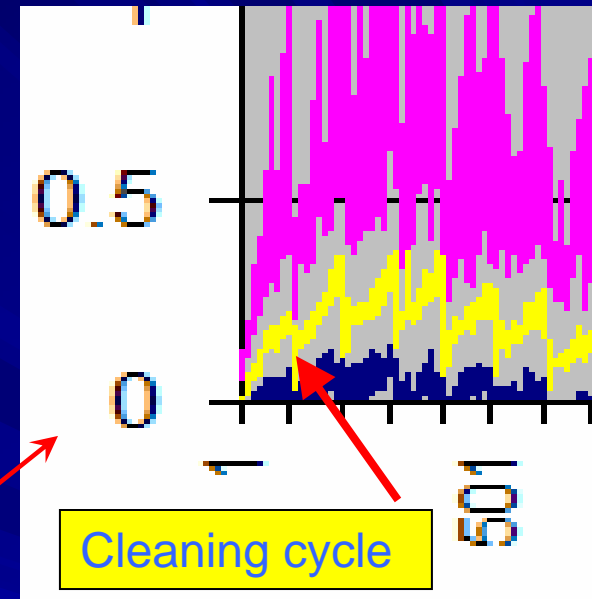
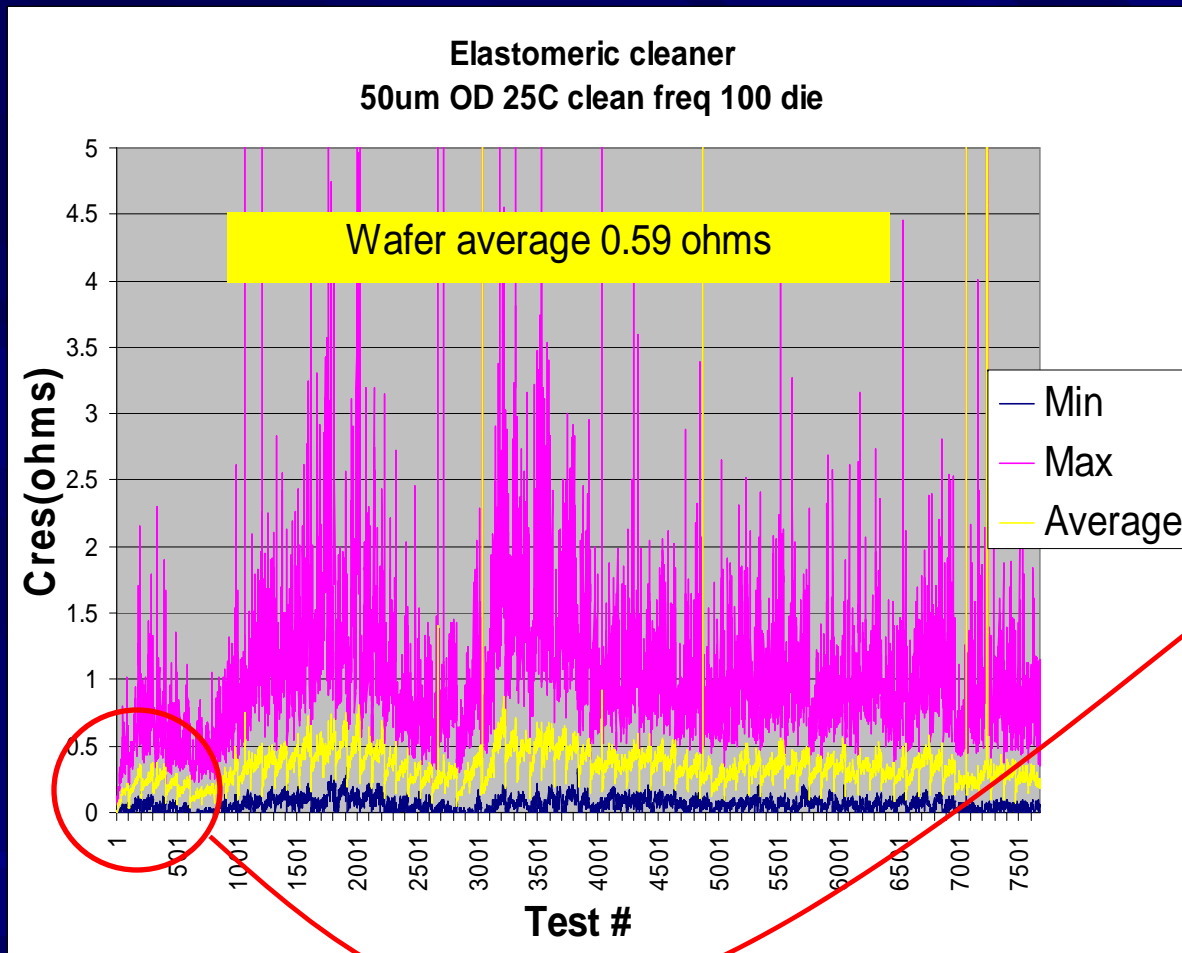
Before clean



After clean

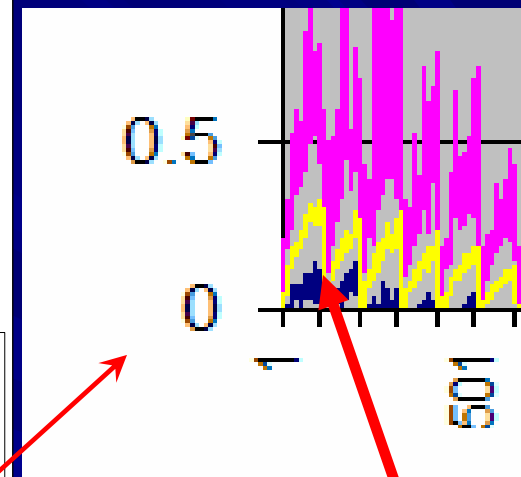
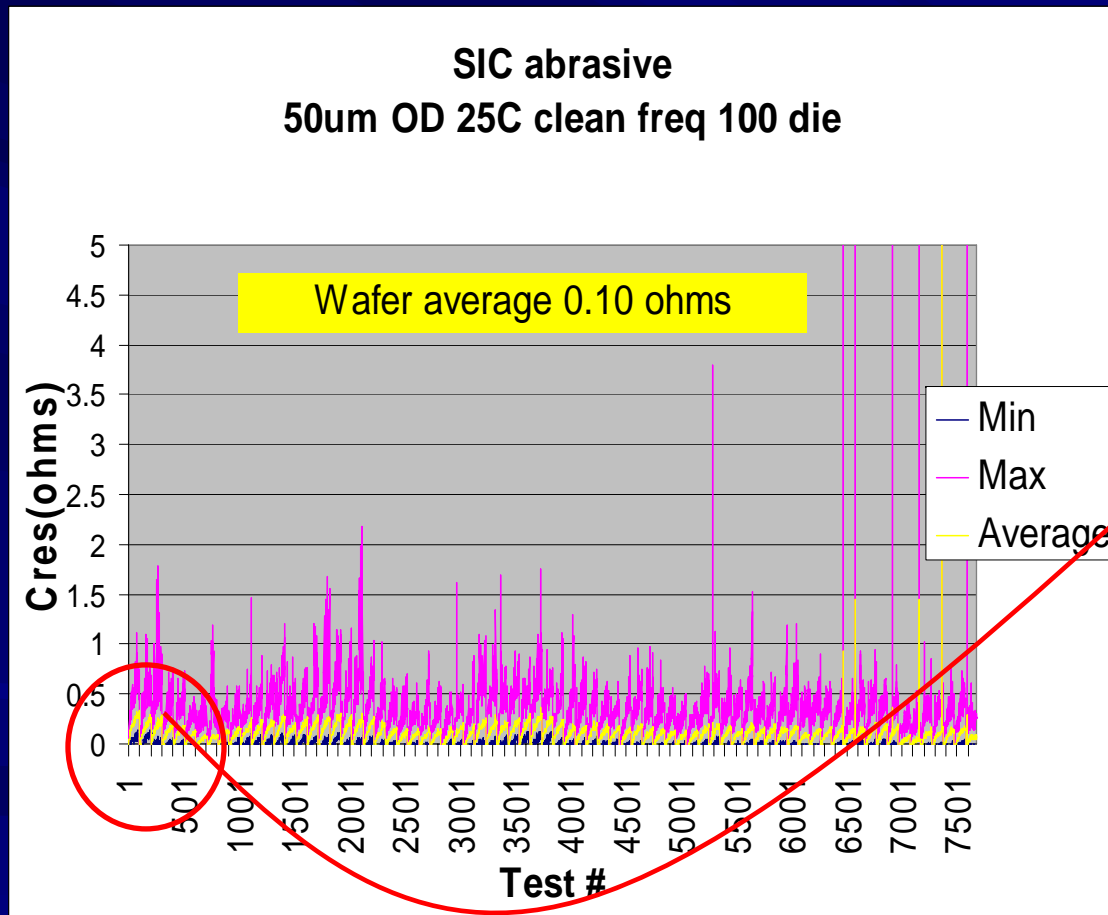


# Contact resistance - Elastomeric



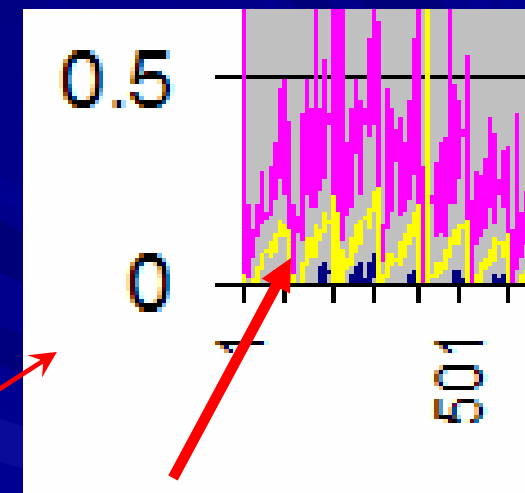
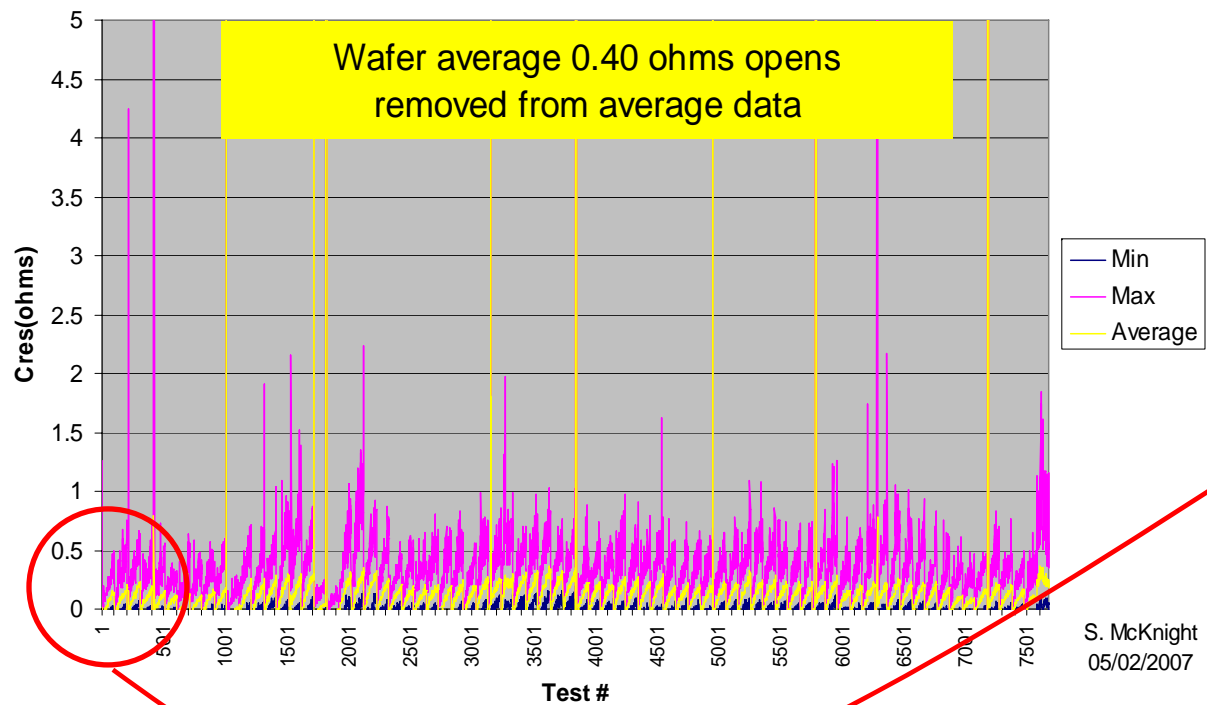
Each "test" represents 25 contacts (190K data points total)  
opens removed from average data – all CRES charts

# Contact resistance – silicon carbi



# Contact resistance – dual clean

JEM elstomeric & SIC abrasive  
50um OD 25C clean freq 100 die  
Each "test" represents 25 contacts (190K data points)



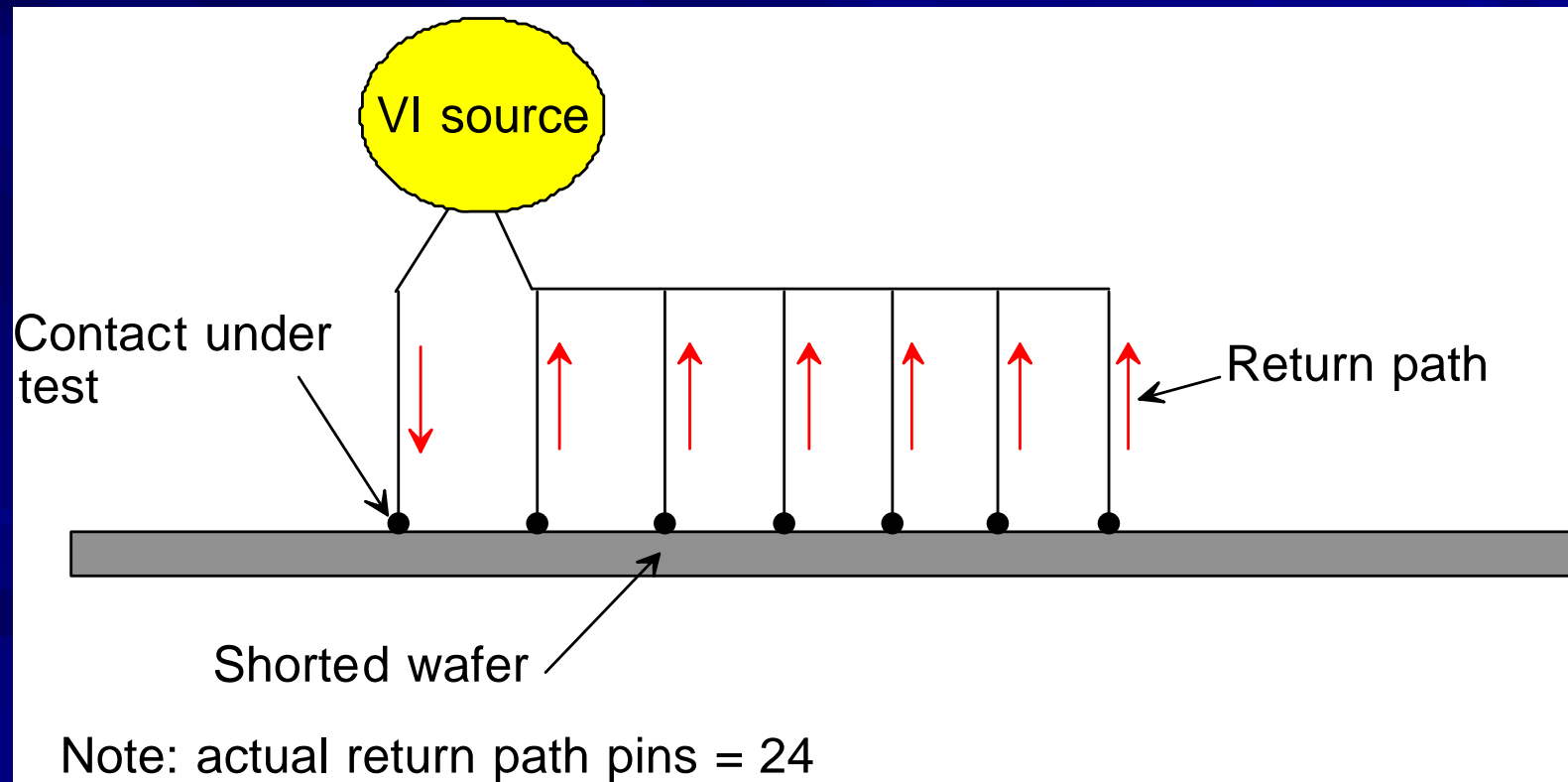
# Contact resistance setup and measurement technique

- TEL P12XLN prober @ 25C, Maximum z velocity
- Probe – 50 micron pitch 1X25 tungsten rhenium material, 20 micron nominal tip diameter ~ 1gf/mil spring rate
- 50 micron overdrive from first touch (contacts were within 9 microns from first to last touch)
- 100 touchdowns between cleans
- Relative measurement – not 4 point
- All data “nulled” – path or bulk resistance removed
- 300mm wafer – 1.2 micron as deposited aluminum – blanket deposition

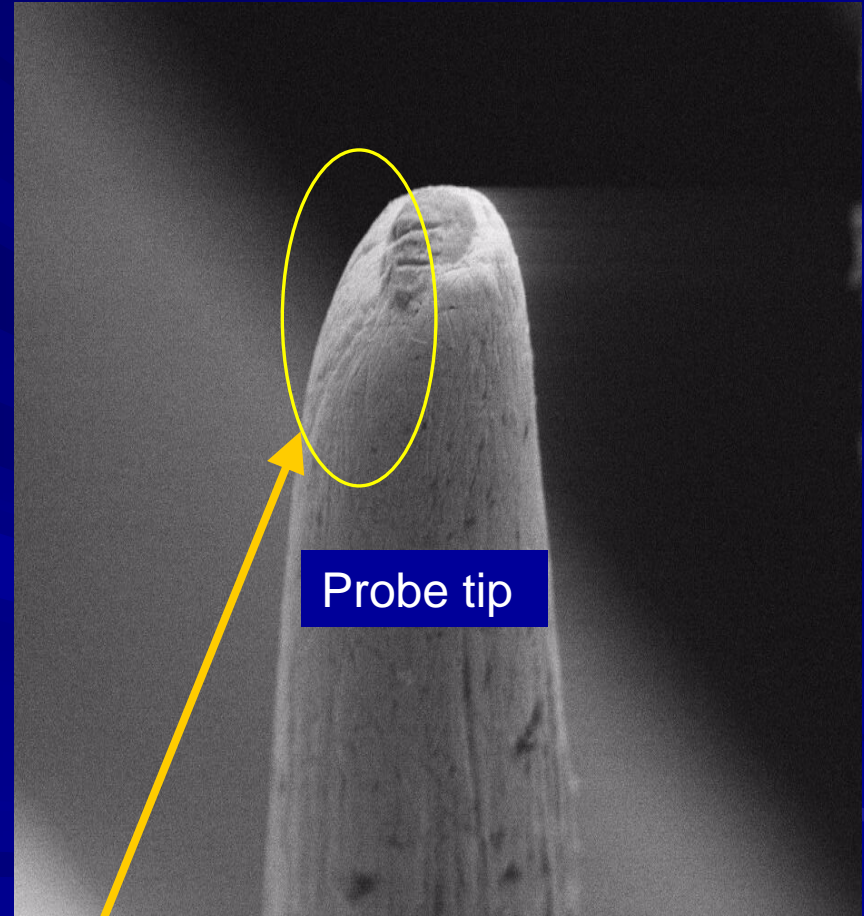


# Measurement circuit

- Test stimulus 10 ma forcing current – 5V clamp
- Min - Max - Average data collected plus raw data
- Keithley based matrix switch and source/measurement unit



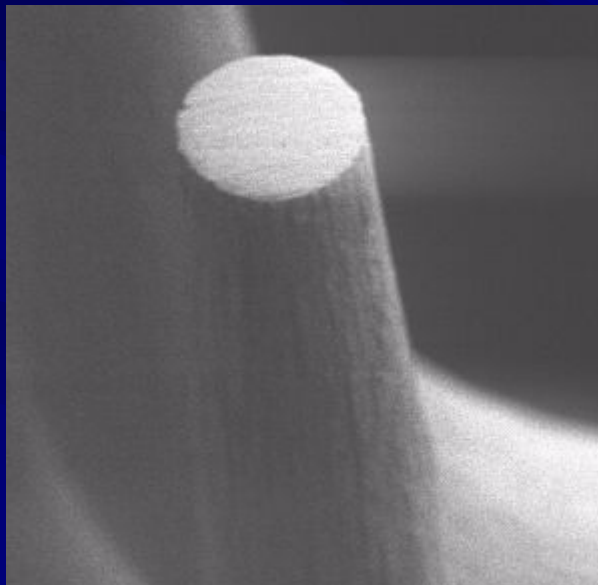
# Polymer based abrasive clean



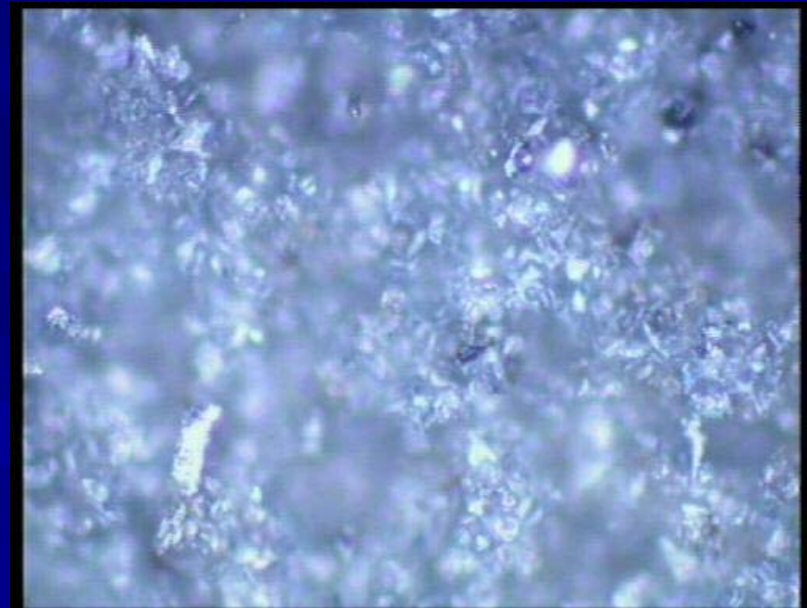
Abraded area – largest area expose to cleaning medium

# SiC clean

Typical flat tip



Silicon Carbide abrasive – 3 $\mu$ m



# “Recipe” Considerations

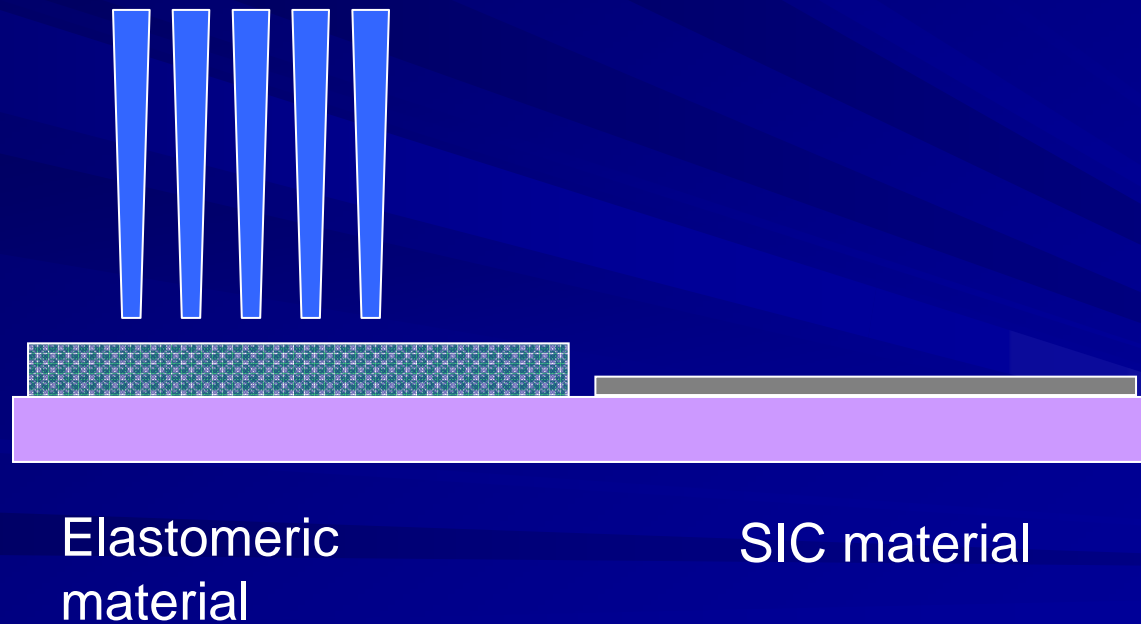
## ■ Probe characteristics

- Tip diameter
- Tip length
- Taper
- Spring rate
- Material

## ■ Cleaning order

- Lowest CRES use SIC last
- Maximum particulate removal use Elastomeric last

# Sequence and motion (use animation)



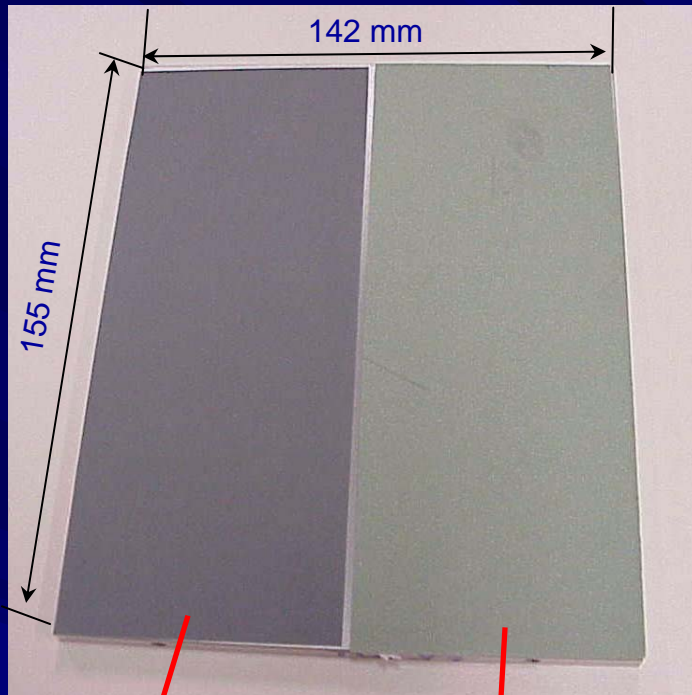
# Benefits

- Low cost solution – use existing materials
- Comparable CRES to SiC material
- Non Silicone
- Uniform tip shape throughout life of probe
- Longer probe life

# Detractor

- Die Size limited – effectively cut cleaning area in half





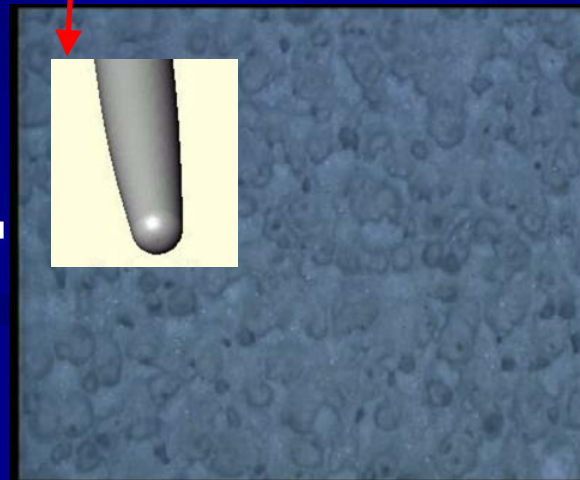
# Cleaning summary

Flat material



June 3, 2007

Radius material



IEEE SW Test Workshop

Semi-Radius tip



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A diagram in the top left corner shows a right-angled triangle with a horizontal base of 142 mm and a vertical height of 155 mm. The dimensions are labeled in blue text with arrows pointing to the respective sides.

# Future work

- Evaluate even lower cost materials
- Look for extension to other probe technologies i.e. Cobra, metrology usage
- Maximize cleaning medium lifetime
- Larger cleaning plate

## Thank you! Questions?